

SYMPOSIUM PROGRAM

Thin film engineering for high-tech labscale and industrial applications

Tuesday 26.11.2024

TIME	TOPIC	LECTURER	INSTITUTION
8:30 - 9:15	Registration	-	-
9:15 - 9:30	Inauguration	Tomasz Szablewski Bartłomiej Witkowski	TECHNOLUTIONS, INSTITUTE OF PHYSICS
9:30 - 9:50	Thin film engineering at the Institute of Physics of the Polish Academy of Sciences	Michał Szot	INSTITUTE OF PHYSICS POLISH ACADEMY OF SCIENCES
9:50 - 10:15	Direct Write Lithography – From Nano to Macro	Daniel Braun	HEIDELBERG INSTRUMENTS
10:15 - 10:40	Scalable Ultrasonic Atomization Systems for Thin-Film Coatings	Bryan Hartz	SONO-TEK CORPORATION
10:40 - 10:55	PVD nanoparticle deposition	Russel Hardy	MOORFIELD NANOTECHNOLOGY LIMITED
10:55 - 11:15	Coffee Break	-	-
11:15 - 11:35	Introduction of Edwards and our products for thin film applications	Russell Coleman	EDWARDS VACUUM
11:35 - 12:05	New developments for dry etching	Andrew Newton	OXFORD INSTRUMENTS
12:05 - 12:25	Nano to Micro: Or How to Combine ALD with PVD	Amit Sharma	SWISS CLUSTER
12:25 - 12:50	Advanced coating equipment - Or how to sputter precise interference filters and dielectric mirrors even on larger substrate formats?	Michael Schneider	VON ARDENNE
12:50 - 13:50	Lunch	-	-
13:50 - 14:05	Anisotropic and isotropic Atomic Layer Etching	Andreas Stamm	OXFORD INSTRUMENTS
14:05 - 15:05	Discussion panel: Electronics and Photonics - two sides of the same coin	Ryszard Piramidowicz Maciej Nowakowski	VIGO PHOTONICS WARSAW UNIVERSITY OF TECHNOLOGY POLISH TECHNOLOGY PLATFORM FOR PHOTONICS
15:05 - 15:30	Efficient and flexible nanopatterning with Variable Shaped Beam lithography	Mathias Haedrich	VISTEC
15:30 - 15:55	Evolution of photovoltaic systems	Paweł Kwaśnicki	ML SYSTEM
15:55 - 17:00	Poster Session	-	-
19:30 - 00:00	Dinner	-	-

Wednesday 27.11.2024

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9:00 - 9:20	Record strength in Materials by combining ALD and PVD	Amit Sharma	SWISS CLUSTER
9:20 - 9:45	Mechanical characterization of thin films by 3D profilometry and scratch testing in semiconductor industries	Philippe Kempe	RTEC-INSTRUMENTS SA
9:45 - 10:05	Flexible metrology solutions for material research	Tunzala Asgarova	KLA INSTRUMENTS GROUP
10:05 - 10:30	Tailoring Atomic Layer Deposition: Versatile Solutions for Diverse Industry Applications	Sanaz Zarabi	BENEQ OY
10:30 - 10:55	Optical and electrical thin film characterization for high-tech lab and industry. Example on GaN – SiC and Perovskite processes and structure	Christophe Defranoux	SEMILAB
10:55 - 11:30	Coffee Break	-	-
11:30 - 11:55	Characterizing the electronic properties at the nanoscale with Pak Systems AFM's	Elena Arbelo	PARK SYSTEMS
11:55 - 12:15	Edwards service offerings for Scientific portfolio	Ivan Maximovic	EDWARDS VACUUM
12:15 - 12:40	Advantages & Combination of automated optical inspection with white light profilometry analysis	Yann Jördens	HIROX EUROPE
12:40 - 13:05	Semiconductor and graphene super-resolution optical imaging	Ivan Urwin	LIG-NANOWISE
13:05 - 14:00	Lunch	-	-
14:00 - 14:25	Zeiss FE-SEM and FIB-SEM for nanofabrication and materials characterization	Olena Vertsanova	CARL ZEISS SP. Z O.O.
14:25 - 14:50	Correlative AFM-in-SEM characterization of low dimensional materials	Veronika Hegrová	NENOVISION S.R.O.
14:50 - 15:15	In situ Extreme Micromechanics – Recent Innovations and Prospects	Renato Pero	ALEMNIS AG
15:15 - 15:35	Novel methods for materials characterisation with Raman spectroscopy	Agnieszka Sozańska	RENISHAW
15:35 - 16:00	The Future of Semiconductors in Poland: How to Develop Alternative Technologies to Silicon	Malwina Szymaniec	IQ WINDOW SP. Z O.O.
16:00 - 16:30	The End / Certificates	Tomasz Szablewski	TECHNOLUTIONS